## **ELECTRONIC INFORMATION DISCLOSURE STATEMENT**

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

METHOD OF CONFLICT AVOIDANCE IN FABRICATION OF GATE-SHRINK ALTERNATING PHASE SHIFTING MASKS

Application Number:

**Confirmation Number:** 

First Named Applicant:

Lars Liebmann

Attorney Docket Number:

FIS920030379

Art Unit:

Examiner:

Search string:

(6277527 or 6523165 or 6541165 or 6569583 or 6584610 or 6593038 or 6622288

).pn

## **US Patent Documents**

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
N	1	6277527	2001-08-21	O'Grady et al.			
120	2	6523165	2003-02-18	Liu et al.			
+X2	3	6541165	2003-04-01	Pierrat			
TX.	4	6569583	2003-05-27	Cho et al.			
	5	6584610	2003-06-24	Wu et al.			
18	6	6593038	2003-07-15	Cho et al.			
	7	6622288	2003-09-16	Wang et al.			

## **Signature**

Examiner Name	Date
Doasco	9/06

Sheet 1 \_\_ of \_1\_ SUPPLEMENTAL INFORMATION DISCLOSURE **SERIAL NO.:** U.S. DEPARTMENT OF COMMERCE **FORM PTO-1449** FIS920030379US1 PATENT AND TRADEMARK OFFICE 10/708,055 (Modified) SUPPLEMENTAL INFORMATION DISCLOSURE APPLICANT: Lars W. Liebmann et al. STATEMENT BY APPLICANT (Use several sheets if necessary) **GROUP:** FILING DATE: 02-05-04 (37 CFR 1.98(b)) **U.S. PATENT DOCUMENTS REFERENCE DESIGNATION** FILING DATE IF SUB-**CLASS** ISSUE EXAMINER **APPROPRIATE CLASS** INITIAL DATE PATENTEE PATENT NUMBER AT AU ΑV AW AX AY AZ **INVENTOR PUBLICATION U.S. PATENT** APPLICATION NO. DATE 03/20/2003 US2003/0056190A1 Liu et al. BA **B8** BC BD **FOREIGN PATENT DOCUMENTS TRANSLATION** SUB-**PUBLICATION COUNTRY OR** CLASS CLASS YES PATENT OFFICE **DOCUMENT NUMBER** DATE

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	BE							
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		OTHER ART	(Including Aut	hor, Title, Date	e, Pertinent Pa	ages, etc.)		
		"Alternating Phase Shifted Mask for Logic Gate Levels, Design and Mask Manufacturing", Lars Liebmann, Io						

Graur, William Liepold, James Oberschmidt, David O'Grady and Denis Riegaill, IBM Microelectronics, 12 pages BJ BK DATE CONSIDERED **EXAMINER** EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to

applicant.

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## SUPPLEMENTAL INFORMATION DISCLOSURE

Sheet <u>1</u> of <u>1</u>

FORM PTO 1449		U.S. DEPARTMENT OF COPPATENT AND TRADEMARK	ATTY. DOCKET NO.: FIS920030379US1		SERIAL NO.: 10/708,055					
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CFR 148	S se	several sheets if necessary)		FILING DATE: February 5, 2004	G	10/708,055  t al.  GROUP: 1756  CLASS SUB- FILING				
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